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Substitute for form 1449A/PTO  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  <i>(use as many sheets as necessary)</i>				<b>Complete If Known</b>	
Application Number		10/694,474			
Filing Date		27 OCTOBER 2003 ✓			
First Named Inventor		Christophe Pierrat et al.			
Group Art Unit		2825			
Examiner Name		LINISUN J.			
Attorney Docket Number		FTIS 1004-1			
Sheet	1	of	2		

U.S. PATENT DOCUMENTS						
Examiner Initials*	Cite No. <sup>1</sup>	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code <sup>2</sup> (if known)			
JL	A1	5,121,256		Corle et al.	06-09-1992	
JL	A2	5,469,299		Nagano	11-21-1995	
JL	A3	5,982,558		Further et al.	11-09-1999	
JL	A4	6,198,576		Matsuyama	03-06-2001	
JL	A5	6,522,484		Schuster	02-18-2003	
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OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.†	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
JSA	C1	FRENCH, ROGER H., et al., "Fluoropolymers for 157nm Lithography: Optical Properties from VUV Absorbance and Ellipsometry Measurements," SPIE Proceedings, Microlithography 2000, 12 pages.	
	C2	FLAGELLO, DONIS G., et al., "High-numerical-aperture effects in photoresist," Applied Optics 36(34) (1 Dec 1997) 8944-8951.	
	C3	FRENCH, ROGER H., et al., "Materials Design and Development of Fluoropolymers for Use as Pellicles in 157nm Photolithography," Optical Microlithography XIV, Proceedings of SPIE vol. 4346 (2001).	
	C4	PIERRAT, CHRISTOPHE, et al., "The MEF Revisited: Low k1 Effects versus Mask Topography Effects," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (25 Feb 2003).	
	C5	CHIBA, YUJI, et al., "New generation projection optics for ArF lithography," Optical Microlithography XV, Proceedings of SPIE Vol. 4691 (2002), 679-686.	
	C6	BAEK, SO-YEON, et al., "Simulation Study of Process Latitude for Liquid Immersion Lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 11 pages.	
	C7	PENDRY, J.B., et al., "Near-field lenses in two dimensions," J. Phys.: Condens. Matter 14 (2002) 8463-8479.	
	C8	OBER, CHRISTOPHER K., "Polymer Surfaces and Surface Analysis," Nanobiotechnology MSE 563/AEP 663 (2000), 43 pages.	
JSA	C9	HAFEMAN, SCOTT, et al., "Simulation of imaging and stray light effects in immersion lithography," Optical Microlithography XVI, Proceedings of SPIE vol. 5040 (27 Feb 2003), 13 pages.	

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Sheet	1	of	2	<table border="1" style="width: 100%; border-collapse: collapse;"> <tr> <td style="width: 50%;">Application Number</td> <td>10/694,474</td> </tr> <tr> <td>Filing Date</td> <td>27 October 2003</td> </tr> <tr> <td>First Named Inventor</td> <td>Christophe Pierrat et al.</td> </tr> <tr> <td>Group Art Unit</td> <td>2825</td> </tr> <tr> <td>Examiner Name</td> <td>LIN, SUN J.</td> </tr> <tr> <td>Attorney Docket Number</td> <td>FTIS 1004-1</td> </tr> </table>	Application Number	10/694,474	Filing Date	27 October 2003	First Named Inventor	Christophe Pierrat et al.	Group Art Unit	2825	Examiner Name	LIN, SUN J.	Attorney Docket Number	FTIS 1004-1
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JSK	A1	6,081,658		Rieger et al.	06-27-2000	
	A2					
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Examiner Signature <span style="font-family: cursive; font-size: 1.2em;">James Sun Bui</span>	Date Considered <span style="font-family: cursive; font-size: 1.2em;">2-8-05</span>
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<p>Substitute for form 1448B/PTO</p> <h2 style="text-align: center;">INFORMATION DISCLOSURE STATEMENT BY APPLICANT</h2> <p style="text-align: center;">(use as many sheets as necessary)</p>		<p><b>Complete If Known</b></p> <table border="1" style="width: 100%; border-collapse: collapse;"><tr><td style="width: 50%;">Application Number</td><td>10/694,474</td></tr><tr><td>Filing Date</td><td>27 October 2003</td></tr><tr><td>First Named Inventor</td><td>Christophe Pierrat et al.</td></tr><tr><td>Group Art Unit</td><td>2825</td></tr><tr><td>Examiner Name</td><td>LIN, SUN J.</td></tr><tr><td>Attorney Docket Number</td><td>FTIS 1004-1</td></tr></table>		Application Number	10/694,474	Filing Date	27 October 2003	First Named Inventor	Christophe Pierrat et al.	Group Art Unit	2825	Examiner Name	LIN, SUN J.	Attorney Docket Number	FTIS 1004-1
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JSA	C1	BRUNNER TIMOTHY A., et al., "Optical/Laser Microlithography VIII," SPIE, Vol. 2440, 301-312.	
JSA	C2	GAROFALO, J., et al., "Automatic Proximity Correction for 0.35Fm I-Line Photolithography," IEEE, Numerical Modeling of Processes and Devices for Integrated Circuits, 1994. NUPAD V., International Workshop on 5-6 Jun 1994, 92-94.	
JSA	C3	RIEGER, MICHAEL L., et al., "Using Behavior Modelling for Proximity Correction," SPIE, 1994, 6 pages.	
JSA	C4	STIRNIMAN, JOHN P., et al., "Fast Proximity Correction with Zone Sampling," SPIE, VOL. 2197, 294-390.	
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JSA	C6	LIEBMANN, L.W. et al., "TCAD development for lithography resolution enhancement," IBM J. RES. & DEV. Vol 45, No. 5, September 2001, 651-665.	
JSA	C7	TORRES, J.A., et al., "Contrast-Based Assist Feature Optimization," Deep Submicron Technical Publication, May 2002, Mentor Graphics, 8 pages.	

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